

## ABSTRACT

An apparatus and method for supporting and precisely positioning a table or stage with respect to a frame. The table is supported by at least one flexible member which is flexible in a plurality of degrees of freedom. The flexible member is  
5 mounted on a base which is movable in an additional degree of freedom. In the context of lithographic semiconductor processing, a wafer stage can thereby be precisely positioned with respect to a frame or reticle in six degrees of freedom.

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